

Supporting information for

A smartphone microscope method for rapid screening of cloth facemask fabrics during pandemics

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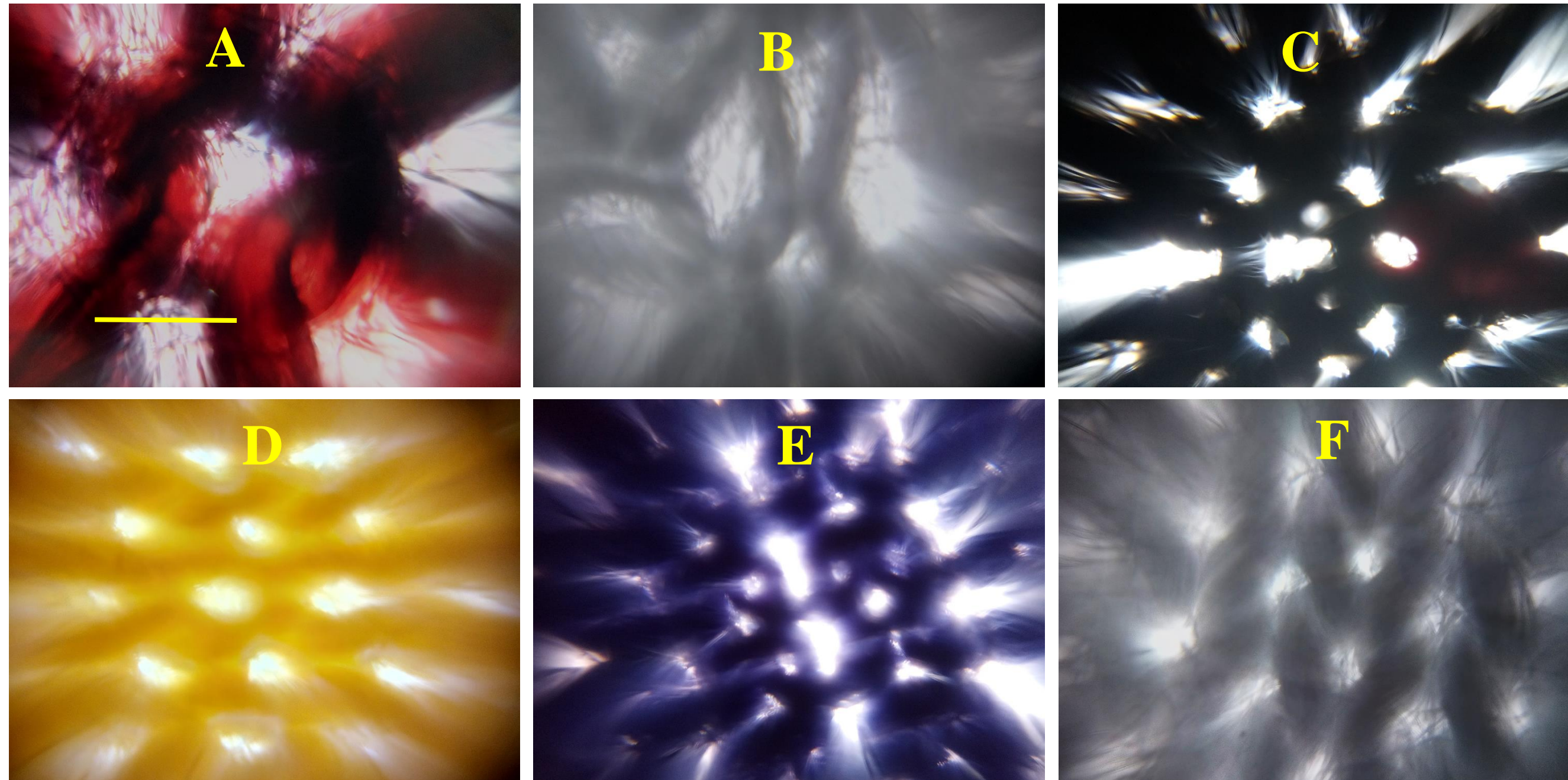
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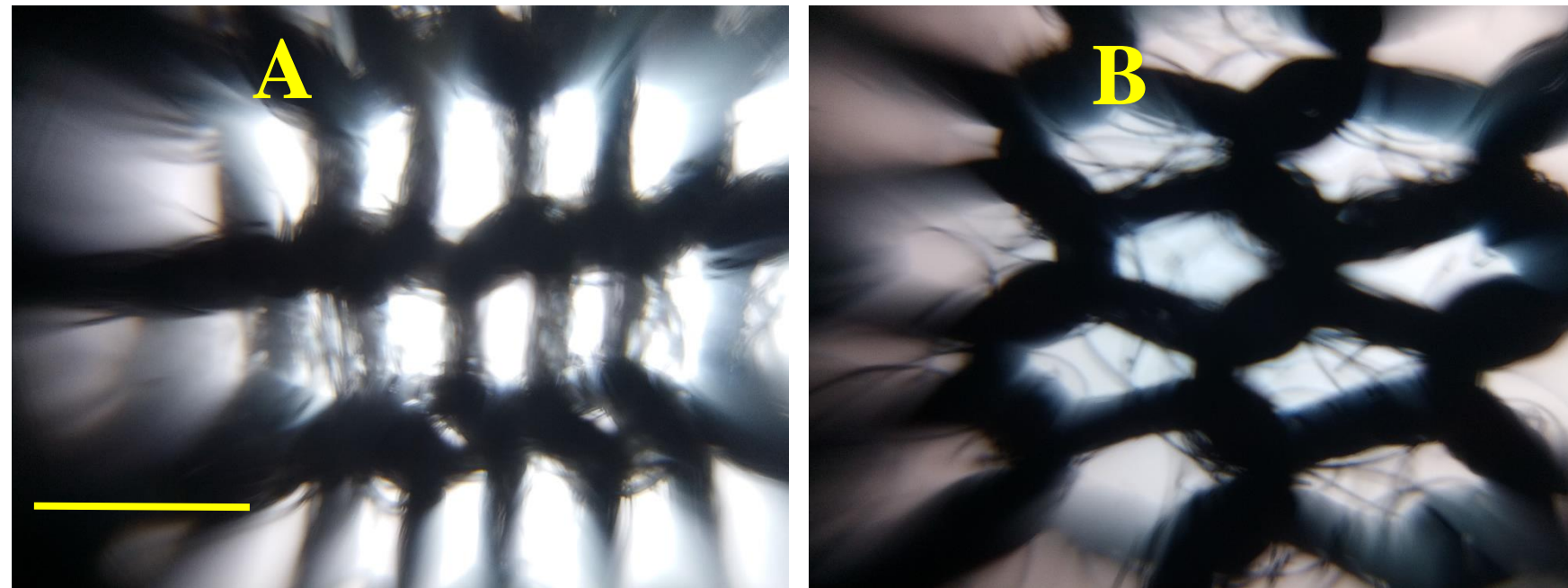
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Supporting figures



Supporting figure 1: Representative images of type I cloth facemask. (A) M3, (B) M4, (C) M7, (D) M8, (E) M9, and (F) M11. The scale bar shown in A is 400 micrometer and applies to all images.



Supporting figure 2: Representative images of type II cloth facemask. (A) layer I (B) layer II of M14. The scale bar shown in A is 400 micrometer and applies to image B also.